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Rho (43) **Pub. Date: Nov. 16, 2006**(54) **DISPLAY PANEL AND METHOD OF
MANUFACTURING THE SAME, AND
TRANSFLECTIVE LIQUID CRYSTAL
DISPLAY WITH THE SAME**(30) **Foreign Application Priority Data**

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SAN JOSE, CA 95134 (US)(51) **Int. Cl.**
G02F 1/1335 (2006.01)(52) **U.S. Cl.** **349/114**(57) **ABSTRACT**

An LCD with a transmission area and a reflection area includes a first substrate, a gate line and a data line formed on the first substrate, a TFT that is connected to the gate line and the data line, a pixel electrode that is connected to the TFT and includes a transparent electrode and a reflective electrode, a second substrate facing the first substrate, a plurality of convex-shaped protrusions that are placed at the reflection area and are formed on the second substrate, and a color filter formed on the protrusions and on the second substrate.

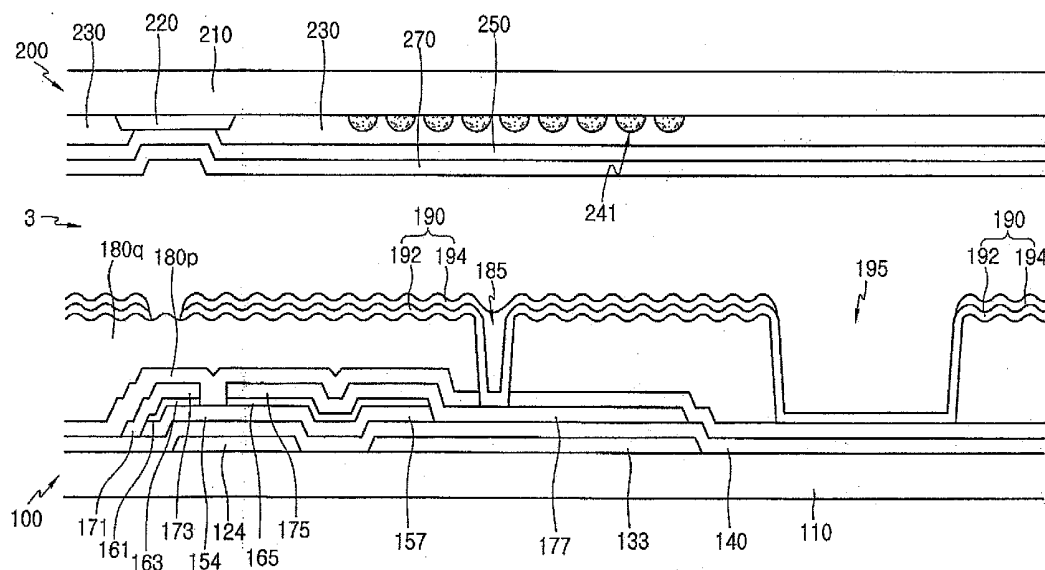
(73) Assignee: **Samsung Electronics Co., LTD.**, Gyeonggi-do (KR)(21) Appl. No.: **11/382,214**(22) Filed: **May 8, 2006**

FIG. 1

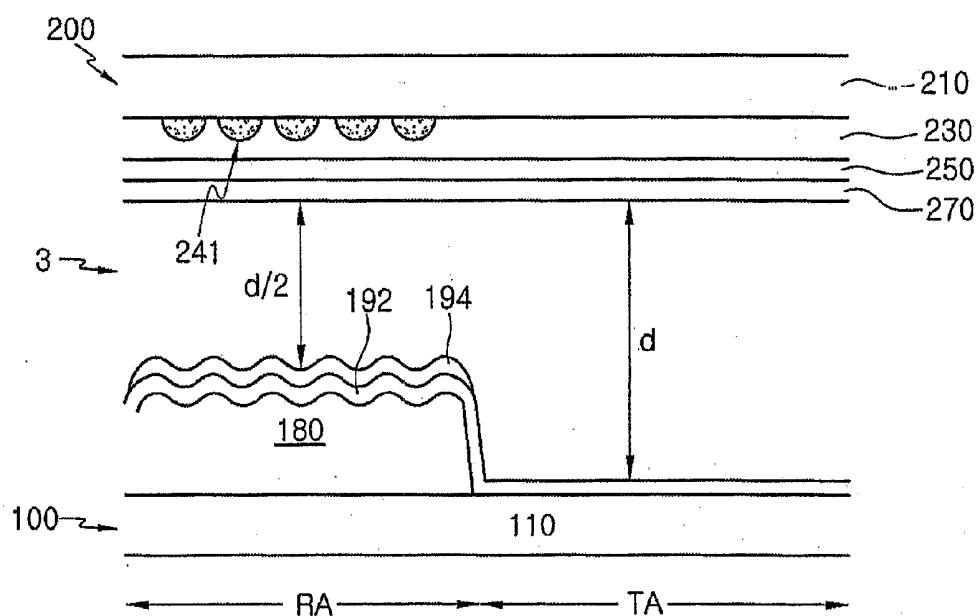


FIG. 2

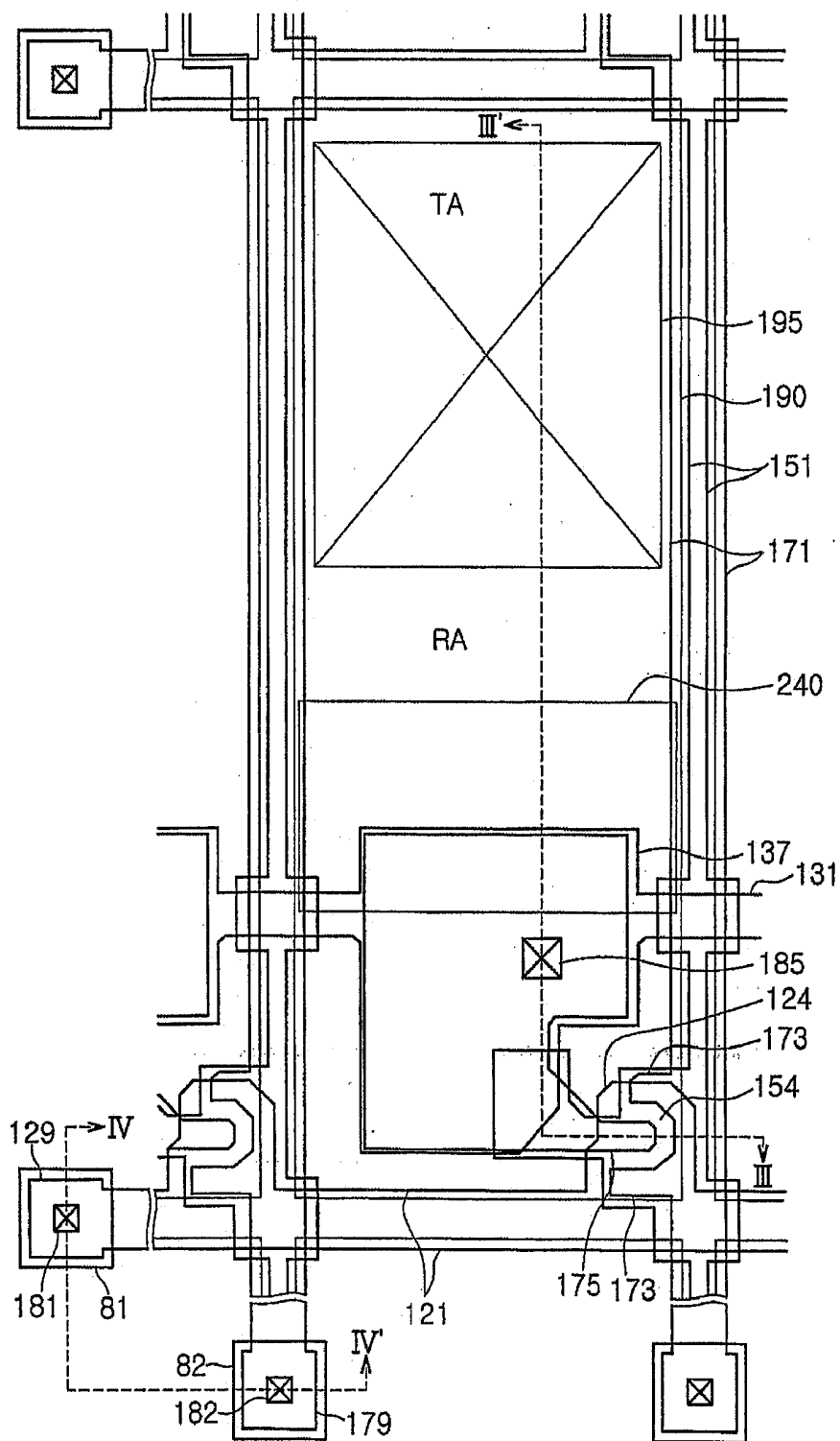


FIG. 3

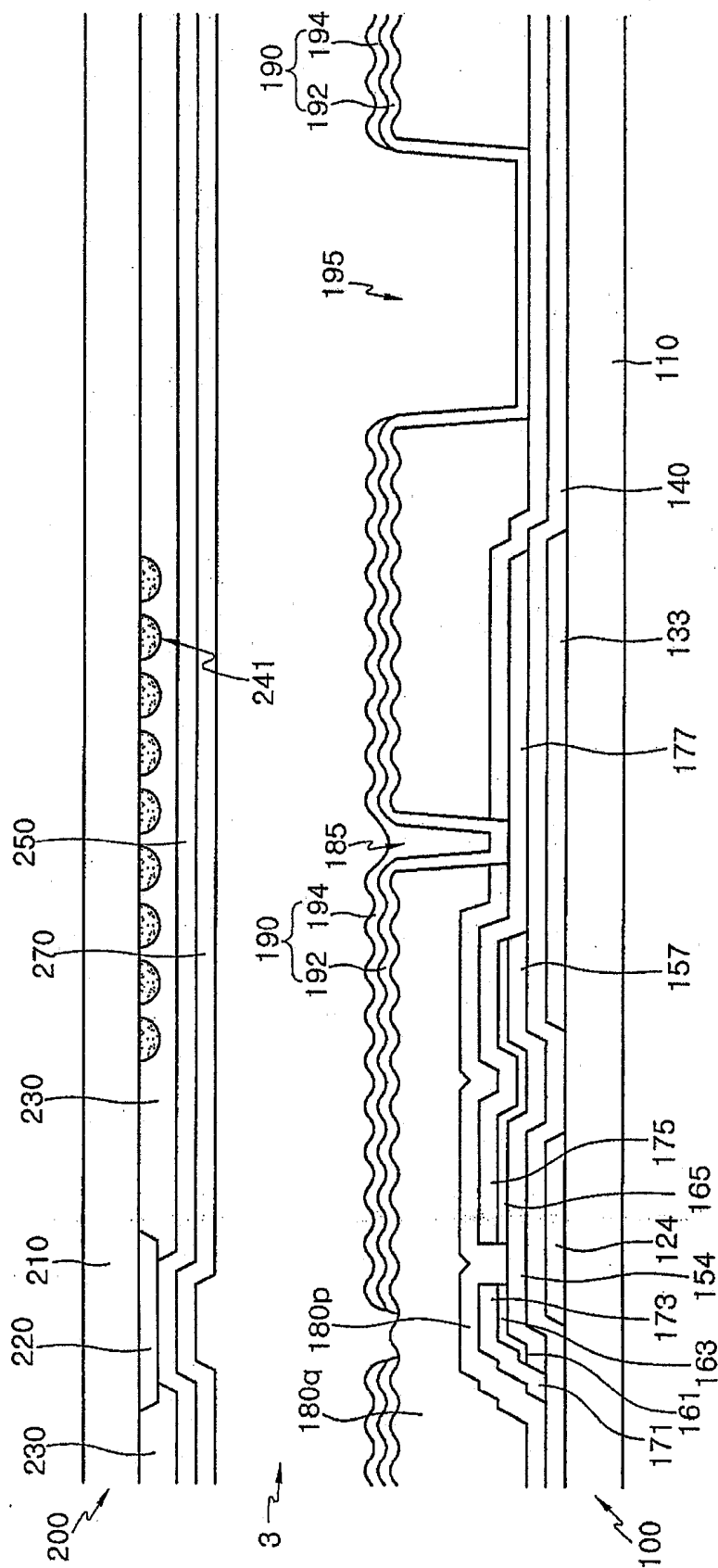


FIG. 4

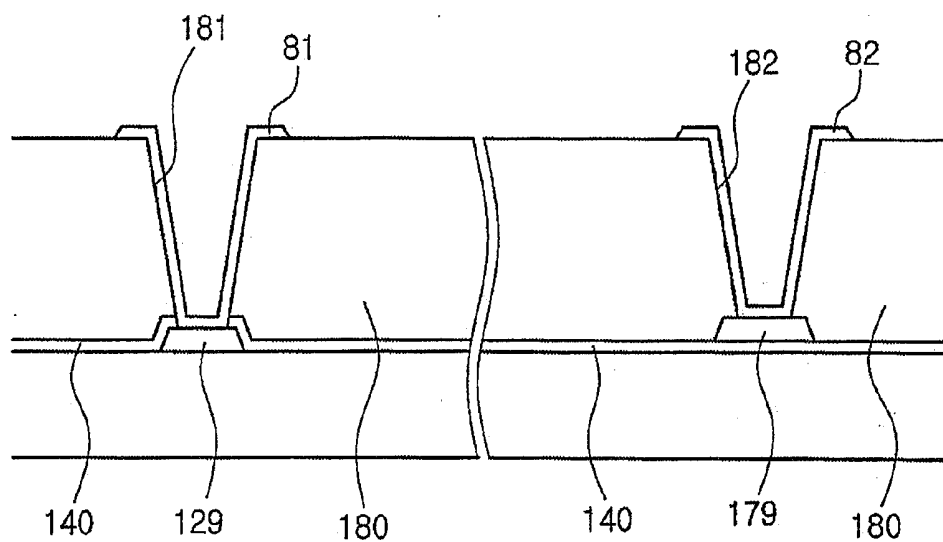


FIG. 5A

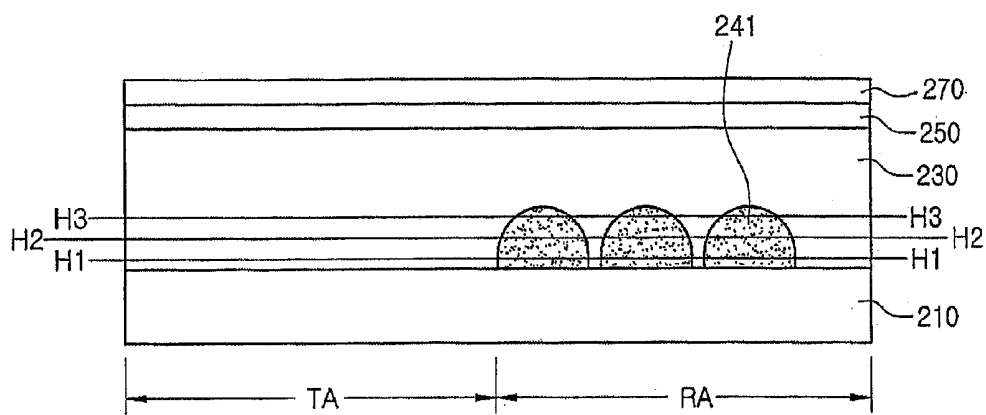


FIG. 5B

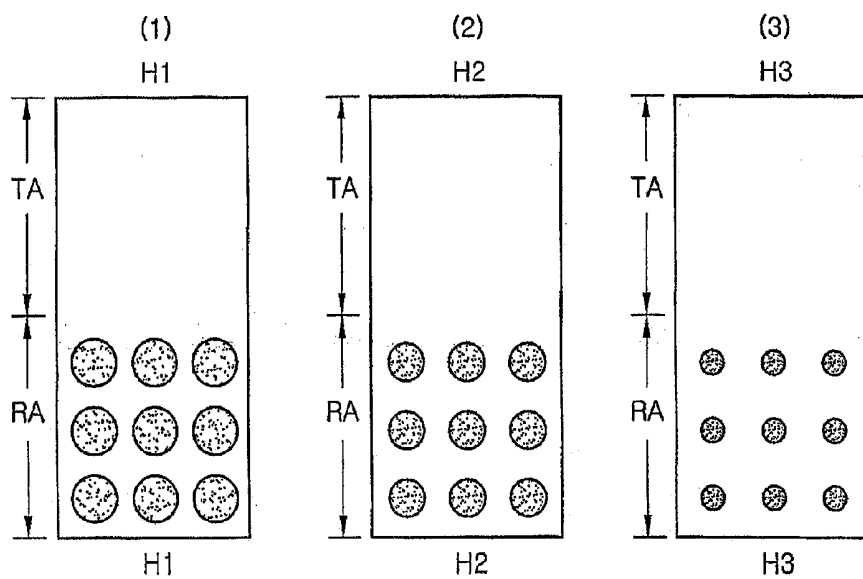


FIG. 6A

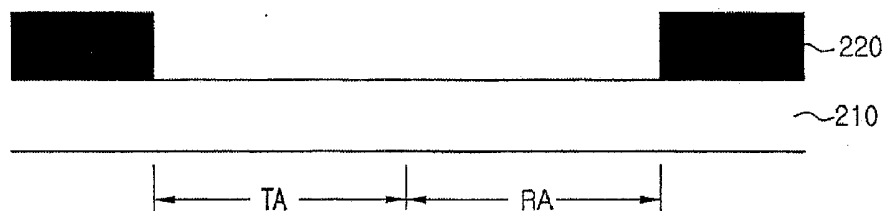


FIG. 6B

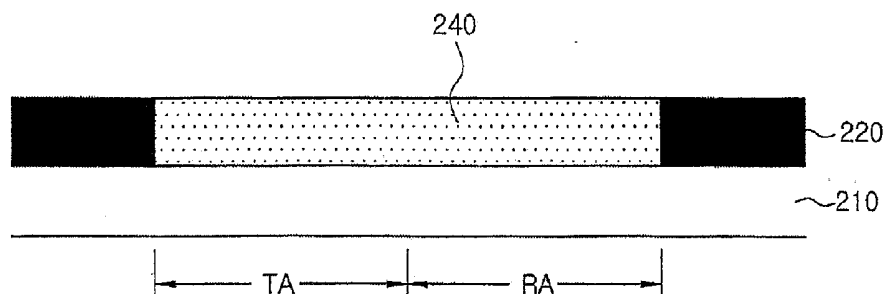


FIG. 6C

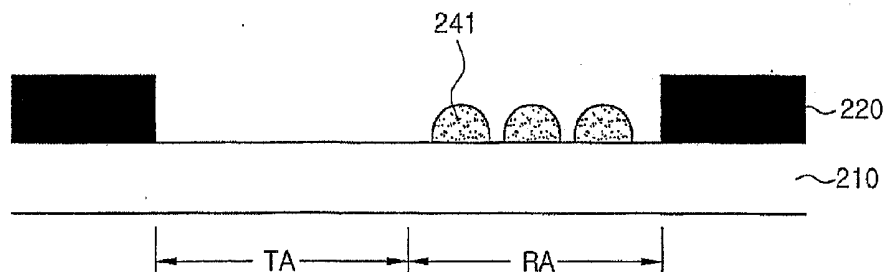


FIG. 6D

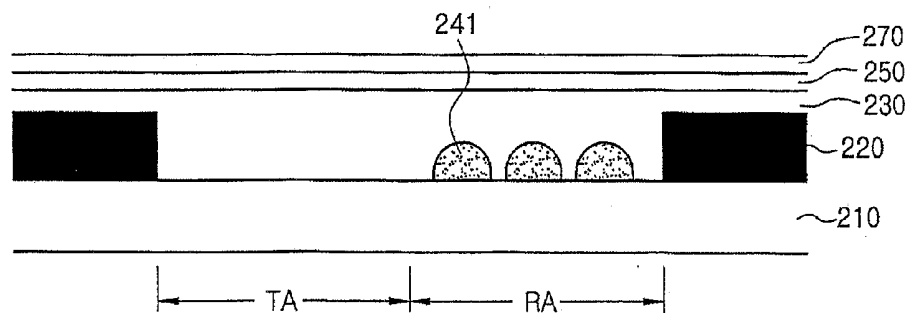
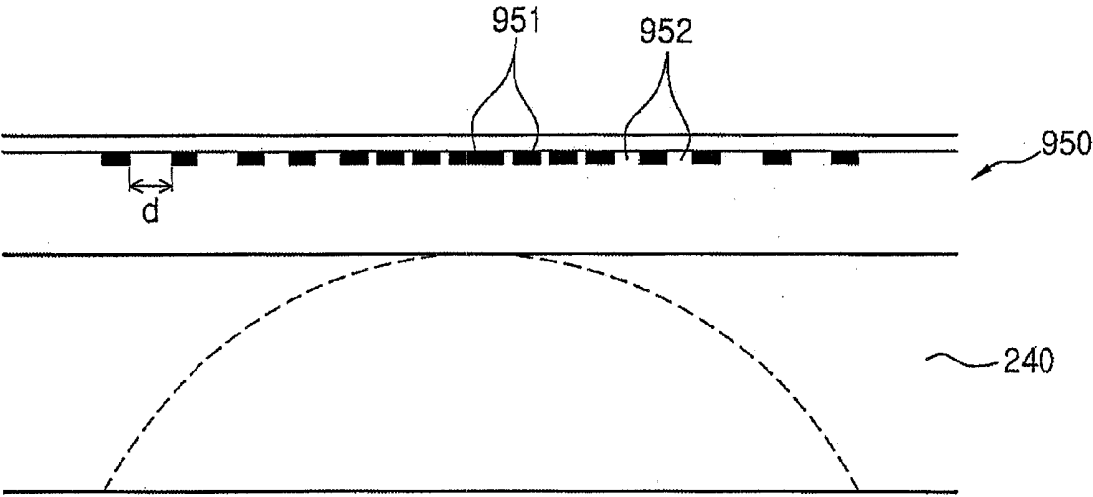


FIG. 7



**DISPLAY PANEL AND METHOD OF
MANUFACTURING THE SAME, AND
TRANSFLECTIVE LIQUID CRYSTAL DISPLAY
WITH THE SAME**

BACKGROUND OF THE INVENTION

[0001] (a) Field of the Invention

[0002] The present invention relates generally to a liquid crystal display (LCD) and, more particularly, to a display panel used for a transfective LCD and a method of manufacturing the same.

[0003] (b) Description of the Related Art

[0004] Generally, an LCD includes a pair of panels each having electrodes formed on the inner surface, and a dielectric anisotropy liquid crystal (LC) layer interposed between the panels. Two polarizers are separately attached to the outer surfaces of the panels. In the LCD, a variation in the strength of an electric field generated by the electrodes changes the orientations of LC molecules in the LC layer, and the orientations of the LC molecules determine the polarization of light passing through the LC layer. At this time, the polarizers either pass or block the polarized light to produce white (or clear) or black (or dark) regions. As a result, a desired image display is realized.

[0005] LCDs are non-emissive displays and they do not produce any form of light. Accordingly, the LCDs utilize artificial light emitted from lamps of a backlight unit separately provided, or ambient light, as a light source.

[0006] Depending on kinds of the light source used for the image display, the LCDs are divided into three types: transmissive, reflective, and transfective (transmissive-reflective). In transmissive LCDs, the pixels are illuminated from behind using a backlight. In reflective LCDs, the pixels are illuminated from the front using incident light originating from the ambient environment. Transfective LCDs combine transmissive and reflective characteristics. Under medium light conditions, such as an indoor environment, or under complete darkness conditions, these LCDs are operated in a transmissive mode, while under very bright conditions, such as an outdoor environment, they are operated in a reflective mode. The reflective and transfective LCDs are commonly used in small and medium size display devices.

[0007] In a transfective LCD, there are transmission areas and reflection areas. In the reflection areas exterior light passes through color filters twice because of reflection, while in the transmission areas light emitted from the backlight that is provided behind an LCD panel assembly passes through the color filter only once. Due to these characteristics, the difference of color tone between the transmission areas and the reflection areas may occur.

[0008] There are two commonly used methods to solve the above-mentioned problem. The first method is to form the color filters of the transmission areas more thickly than the color filters of the reflection areas. The second method is to form light holes in the color filters of the reflection areas.

[0009] However, the latter method has some drawbacks. In this method, after the formation of the holes, an overcoat layer is coated on all the color filters in order to compensate a step difference between the color filters with the holes and

the color filters without the holes and thus to create a planarized surface. In this case, however, perfect planarization is technically impossible. Accordingly, even if the overcoat layer is formed on all the color filters, a cell gap at the reflection area with the holes and a cell gap at the transmission area without the holes are different from each other. Also, the common electrode is depressed in the vicinities of the holes. Accordingly, the orientations of the LC molecules become poor and those molecules may be abnormally operated.

SUMMARY OF THE INVENTION

[0010] The present invention reduces a difference of color tone between a transmission area and a reflection area.

[0011] According to an aspect of the present invention, there is provided a display panel for a transfective LCD with a transmission area and a reflection area, including a substrate, a plurality of convex-shaped protrusions that are formed on the substrate and are placed at the reflection area, and a color filter formed on the protrusions and the substrate.

[0012] In this structure, the protrusions may include a transparent organic material. Each protrusion may have a diameter of 10 μm to 15 μm and a height of 1 μm to 2 μm , and the protrusions may have the same size or different sizes.

[0013] The color filter may have a flat top surface.

[0014] The display panel may further include a light-blocking member that is formed on the substrate.

[0015] The display panel may further include a common electrode that is formed on the color filter.

[0016] The display panel may further include an overcoat layer that is formed between the color filter and the common electrode.

[0017] According to another aspect of the present invention, there is provided an LCD with a transmission area and a reflection area, including a first substrate, a gate line and a data line that are formed on the first substrate, a thin film transistor (TFT) that is connected to the gate line and the data line, a pixel electrode that is connected to the TFT and includes a transparent electrode and a reflective electrode, a second substrate that is opposite to the first substrate, a plurality of convex-shaped protrusions that are placed at the reflection area and are formed on the second substrate, and a color filter formed on the protrusions and on the second substrate.

[0018] In this structure, the protrusions may include a transparent organic material. Each protrusion may have a diameter of 10 μm to 15 μm and a height of 1 μm to 2 μm , and the protrusions may have the same size or different sizes.

[0019] The color filter may have a flat top surface.

[0020] The transparent electrode is formed at the transmission area and the reflection area, while the reflective electrode is formed at the reflection area. The reflective electrode is formed on the transparent electrode.

[0021] The LCD may further include an upper passivation layer and a lower passivation layer that are formed between the TFT and the pixel electrode. The upper passivation layer

may include an aperture where the lower passivation layer is exposed, and it may have an uneven top surface.

[0022] The LCD may further include a light-blocking member that is formed on the second substrate.

[0023] The LCD may further include a common electrode that is formed on the color filter.

[0024] The LCD may further include an overcoat layer that is formed between the color filter and the common electrode.

[0025] According to still another aspect of the present invention, there is provided a method of manufacturing a display panel for an LCD, which includes the steps of providing a substrate, forming convex-shaped protrusions on the substrate, and forming a color filter on the protrusions and the substrate.

[0026] The step of forming convex-shaped protrusions includes forming a photosensitive organic layer over the substrate, selectively exposing the substrate to light through a mask, developing the substrate, and baking the substrate.

[0027] The mask used in the step of forming convex-shaped protrusions may be a slit-type mask.

[0028] Each protrusion may have a diameter of 10 μm to 15 μm and a height of 1 μm to 2 μm , and the protrusions may have the same size or different sizes.

[0029] The color filter may have a flat top surface.

[0030] The step of forming a light-blocking member on the substrate may be further included in this method.

[0031] The step of forming a common electrode on the color filter may be further included in this method.

[0032] The step of forming an overcoat layer that is formed between the color filter and the common electrode may be further included in this method.

BRIEF DESCRIPTION OF THE DRAWINGS

[0033] The above objects and other advantages of the present invention will become more apparent by describing the preferred embodiments thereof in more detail with reference to the accompanying drawings.

[0034] **FIG. 1** is a schematic cross-sectional view of an LCD according to an embodiment of the present invention.

[0035] **FIG. 2** is a layout view of an LCD according to an embodiment of the present invention.

[0036] **FIG. 3** is a cross-sectional view cut along III-III' of **FIG. 2**.

[0037] **FIG. 4** is a cross-sectional view cut along IV-IV' of **FIG. 2**.

[0038] **FIG. 5A** shows a vertical scheme of a common electrode panel according to an embodiment of the present invention.

[0039] **FIG. 5B** shows three horizontal cross-sections cut along H1-H1, H2-H2, and H3-H3 of **FIG. 5A**.

[0040] **FIG. 6A through 6D** are cross-sectional views showing process steps to manufacture a common electrode panel according to an embodiment of the present invention.

[0041] **FIG. 7** shows a slit-type mask used in an embodiment of the present invention.

DETAILED DESCRIPTION OF THE PREFERRED EMBODIMENTS

[0042] Preferred embodiments of the present invention will be described more fully hereinafter with reference to the accompanying drawings, in which preferred embodiments of the invention are shown. The present invention may, however, be embodied in different forms and should not be construed as being limited to the embodiments set forth herein. Rather, these embodiments are provided so that this disclosure will be thorough and complete, and will fully convey the scope of the invention to those skilled in the art.

[0043] In the drawings, the thickness of the layers, films, and regions are exaggerated for clarity. Like numerals refer to like elements throughout. It will be understood that when an element such as a layer, film, region, or substrate is referred to as being "on" another element, it can be directly on the other element or intervening elements may also be present.

[0044] Hereinafter, an LCD according to a preferred embodiment of the present invention will be described in detail with reference to accompanying drawings.

[0045] **FIG. 1** is a schematic cross-sectional view of an LCD according to an embodiment of the present invention.

[0046] Referring to **FIG. 1**, the LCD of this embodiment comprises a TFT array panel **100** and a common electrode panel **200** facing each other, and an LC layer **3** interposed therebetween.

[0047] The TFT array panel **100** comprises an insulating substrate **110**, switching elements (not shown) and a passivation layer **180** formed on the insulating layer **110**, and pixel electrodes **190** formed on the passivation layer **180**. Each pixel electrode **190** is comprised of a transparent electrode **192** and a reflective electrode **194** overlying a partial portion of the transparent electrode **192**.

[0048] The common electrode panel **200** comprises an insulating substrate **210**, and color filters **230**, an overcoat **250** and a common electrode **270** formed on the substrate **210**.

[0049] In a transreflective LCD, there are transmission areas TA defined by the transparent electrodes **192** and reflection areas RA defined by the reflective electrodes **194**. In more detail, the transmission area TA is a section of portions disposed on and under an exposed portion of the transparent electrodes **192** in the TFT array panel **100**, the common electrode panel **200**, and the LC layer **3**, while the reflection area RA is a section of portions disposed on and under the reflective electrode **194**. In the transmission areas TA, internal light, emitted from the rear of the LCD, successively passes through the TFT panel **100** and the LC layer **3** and then exits the common electrode panel **200**, thus contributing to the display. In the reflection areas RA, exterior light, supplied through the front of the LCD, successively passes through the common electrode panel **200** and the LC layer **3** and is then reflected by the reflective electrodes **194** of the TFT panel **100**. After the reflection, the exterior light passes through the LC layer **3** again and then exits the common electrode panel **200**, thus contributing to the display.

[0050] In each reflection area RA, a group of convex-shaped protrusions 241 are formed between the lower substrate 210 and the color filter 230. The sizes of the protrusions 241 may be exactly equal to or different from each other. The protrusions 241 have very small diameters. Each protrusion 241 is formed to be similar to a hemisphere where its height is maximized at its center and decreases as a height-measuring point recedes from the center, and where its plane dimension is maximized at its bottom surface and decreases to a point at its top center as a dimension-measuring point recedes from the bottom surface.

[0051] The maximum heights of the protrusions 241 are much smaller than the thickness of the color filters 230 directly overlying the protrusions 241. For this reason, the color filters 230 can be planarized regardless of the protrusions 241, and thus a cell gap can be uniformly formed over the entire area of the display. In addition, due to the protrusions 241 formed at the reflection areas RA, the color filters 230 placed at the reflection areas RA are more thinly formed than the color filters 230 placed at the transmission areas TA. That is, the average thickness of the color filters 230 that are placed at the reflection areas RA becomes smaller than that of the color filters 230 that are placed at the transmission areas TA. Accordingly, the color filters 230 formed in this manner can reduce a difference of color tone occurring between the transmission areas TA and the reflection areas RA.

[0052] Hereinafter, the basic structure of the above-mentioned LCD will be described in more detail with reference to FIG. 2 through FIG. 4.

[0053] FIG. 2 is a layout view of an LCD according to an embodiment of the present invention, and FIG. 3 and FIG. 4 are cross-sectional views cut along III-III' and IV-IV' of FIG. 2, respectively.

[0054] Referring to FIG. 2 to FIG. 4, the LCD includes a TFT array panel 100 and a common electrode panel 200 facing each other, and an LC layer 3 interposed therebetween.

[0055] The TFT array panel 100 is configured as follows.

[0056] A plurality of gate lines 121 and a plurality of storage electrode lines 131 are formed on an insulating substrate 110 made of transparent glass or plastic.

[0057] The gate lines 121 for transmitting gate signals extend substantially in a horizontal direction. Each gate line 121 includes a plurality of gate electrodes 124 protruding upward and an end portion 129 having a relatively large dimension to be connected to a different layer or an external device. A gate driver (not shown) for generating the gate signals may be mounted on a flexible printed circuit (not shown) attached to the substrate 110, or mounted directly on the substrate 110. Otherwise, the gate driver may be integrated into the substrate 110. In this case, the gate lines 121 are directly connected to the gate driver.

[0058] The storage electrode lines 131 for receiving a predetermined voltage extend substantially parallel to the gate lines 121 and have a plurality of storage electrodes 133. Each storage electrode line 131 is placed between two adjacent gate lines, and in particular, closer to the lower-positioned gate line of the two. Each storage electrode line 131 includes a plurality of expansions 137 protruding

upward and downward. The form and arrangement of the storage electrode lines 131 may be varied in other embodiments.

[0059] The gate lines 121 and the storage electrode lines 131 are preferably made of an aluminum (Al) containing metal such as Al and an Al alloy, a silver (Ag) containing metal such as Ag and a Ag alloy, a gold (Au) containing metal such as Au and a Au alloy, a copper (Cu) containing metal such as Cu and a Cu alloy, a molybdenum (Mo) containing metal such as Mo and a Mo alloy, chrome (Cr), titanium (Ti), or tantalum (Ta). The gate lines 121 and the storage electrode lines 131 may be configured as a multi-layered structure, in which at least two conductive layers (not shown) having different physical properties are included. In such a structure, one of the two conductive layers is made of a low resistivity metal, such as an Al-containing metal, a Ag-containing metal, a Cu-containing metal, or the like, in order to reduce delay of the signals or voltage drop in the gate lines 121 and the storage electrode lines 131. The other is made of a material having prominent physical, chemical, and electrical contact properties with other materials such as indium tin oxide (ITO), indium zinc oxide (IZO), etc. For example, a Mo containing metal, Cr, Ta, or Ti, etc., may be used for the formation of the same layer. Desirable examples of the combination of the two layers are a lower Cr layer and an upper Al (or Al alloy) layer, and a lower Al (or Al alloy) layer and an upper Mo (or Mo alloy) layer. Besides the above-listed materials, various metals and conductors can be used for the formation of the gate lines 121 and the storage electrode lines 131.

[0060] All lateral sides of the gate lines 121 and the storage electrode lines 131 preferably slope in the range from about 30° to 80° to the surface of the substrate 110.

[0061] A gate insulating layer 140 made of silicon nitride (SiN_x) or silicon oxide (SiO_x) is formed on the gate lines 121 and the storage electrode lines 131.

[0062] A plurality of linear semiconductors 151 made of hydrogenated amorphous silicon (abbreviated as "a-Si") or polysilicon are formed on the gate insulating layer 140. Each linear semiconductor 151 extends substantially in a vertical direction, and includes a plurality of projections 154 that extend along the respective gate electrodes 124 and have sub-projections 157 extending toward the expansions 137 of the storage electrode lines 131. The linear semiconductors 151 are enlarged in the vicinities of the gate lines 121 and the storage electrode lines 131 to cover them widely.

[0063] A plurality of linear ohmic contacts 161 and island-shaped ohmic contacts 165 are formed on the linear semiconductors 151. The ohmic contacts 161 and 165 may be made of N⁺ hydrogenated amorphous silicon that is highly doped with N-type impurities such as phosphorus (P), or silicide. The linear ohmic contacts 161 include a plurality of projections 163. A set of a projection 163 and an island-shaped ohmic contact 165 is placed on the projection 154 of the semiconductor 151.

[0064] All lateral sides of the semiconductors 151 and the ohmic contacts 163 and 165 slope in the range from about 30° to 80° to the surface of the substrate 110.

[0065] A plurality of data lines 171 and a plurality of drain electrodes 175 are formed on the ohmic contacts 163 and 165 and the gate insulating layer 140.

[0066] The data lines 171 for transmitting data signals extend substantially in a vertical direction to be crossed with the gate lines 121 and the storage electrode lines 131. Each data line 171 includes a plurality of source electrodes 173 extending toward the respective gate electrodes 124, and an end portion 179 having a relatively large dimension to be connected to a different layer or an external device. A data driver (not shown) for generating the data signals may be mounted on a flexible printed circuit (not shown) attached to the substrate 110, or mounted directly on the substrate 110. Otherwise, the data driver may be integrated into the substrate 110. In this case, the data lines 171 are directly connected to the gate driver.

[0067] The drain electrodes 175 separated from the data lines 171 are opposite to the source electrodes 173, centering on the gate electrodes 124. Each drain electrode 175 includes an expansion 177 having a relatively large dimension and a bar-shaped end portion. The expansions 177 of the drain electrodes 175 are overlapped with the expansions 137 of the storage electrode lines 131, and the bar-shaped end portions are partially surrounded with the curved source electrodes 173.

[0068] A gate electrode 124, a source electrode 173, a drain electrode 175, and a projection 154 of the semiconductor 151 form a thin film transistor (TFT). A TFT channel is formed in the projection 154 provided between the source electrode 173 and the drain electrode 175.

[0069] The data lines 171 and the drain electrodes 175 are preferably made of a refractory metal such as Mo, Cr, Ta, or Ti, or alloys thereof, and may be configured as multi-layered structures including a refractory metal layer (not shown) and a low resistivity conductive layer (not shown). A desirable example of the multi-layered structure is a lower layer made of one among Cr, Mo, and a Mo alloy, and an upper layer made of Al or an Al alloy. Another example is a lower layer made of Mo or a Mo alloy, an intermediate layer made of Al or an Al alloy, and an upper layer made of Mo or a Mo alloy. Besides the above-listed materials, various metals and conductors can be used for the formation of the data lines 171 and the drain electrodes 175.

[0070] All lateral sides of the data lines 171 and the drain electrodes 175 preferably slope in the range from about 30° to 80° to the surface of the substrate 110.

[0071] The ohmic contacts 163 and 165 exist only between the underlying semiconductors 151 and the overlying data lines 171 and between the overlying drain electrodes 175 and the underlying semiconductors 151, in order to reduce contact resistance therebetween. Most of the linear semiconductors 151 are formed more narrowly than the data lines 171, but partial portions thereof are enlarged in the vicinities of places to be crossed with the gate lines 121, as previously mentioned, in order to prevent the data lines 171 from being shorted. The linear semiconductors 151 are partially exposed at places where the data lines 171 and the drain electrodes 175 do not cover them, as well as between the source electrodes 173 and the drain electrodes 175.

[0072] A passivation layer 180 is formed on the data lines 171, the drain electrodes 175, and the exposed portions of the semiconductors 151. The passivation layer 180 is configured as a double-layered structure including a lower layer 180p made of an inorganic insulator such as SiN_x or SiO_x,

and an upper layer 180q made of an organic insulator. A desirable organic insulator for the upper passivation layer 180q has a low dielectric constant of below 4.0 and/or photosensitivity. The upper passivation layer 180q is provided with apertures 195 where the lower passivation layer 180p is partially exposed, and the top surface of the upper passivation layer 180q is uneven. The passivation layer 180 may be configured as a single layer made of an inorganic insulator or an organic insulator.

[0073] The passivation layer 180 is provided with a plurality of contact holes 182 and 185, through which the end portions 179 of the data lines 171 and the drain electrodes 175 are exposed, respectively. A plurality of contact holes 181 are formed in the passivation layer 180 and the gate insulating layer 140, and the end portions 129 of the gate lines 121 are exposed therethrough.

[0074] A plurality of pixel electrodes 190 and a plurality of contact assistants 81 and 82 are formed on the passivation layer 180.

[0075] Each pixel electrode 190 has a ripple-shaped profile caused by the uneven top surface of the upper passivation layer 180q, and is comprised of a transparent electrode 192 and a reflective electrode 194 overlying the transparent electrode 192. The transparent electrodes 192 are made of a transparent conductor such as ITO or IZO, and the reflective electrodes 194 are made of an opaque reflectivity conductor such as Al, Cr, Ag, or alloys thereof. However, the reflective electrodes 194 may be configured as a double-layered structure. In this case, upper layers are made of a low resistivity metal such as Al, Ag, a Ag alloy, or the like, and lower layers are made of a material having prominent contact properties with ITO and IZO, such as a Mo-containing metal, Cr, Ta, Ti, or the like.

[0076] Each reflective electrode 194 is formed only on a partial portion of the transparent electrode 192. Accordingly, the remaining portion the transparent electrode 192 is exposed. At this time, the exposed portion of the transparent electrode 192 is disposed to correspond to the aperture 195 of the upper passivation layer 180q.

[0077] The pixel electrodes 190 are physically and electrically connected to the drain electrodes 175 through the contact holes 185 in order to receive data voltages from the drain electrodes 175. The pixel electrodes 190 supplied with the data voltages generate electric fields in cooperation with a common electrode 270 of the common electrode panel 200, determining the orientations of the LC molecules in the LC layer 3 interposed between the two electrodes 190 and 270. According to the orientations of the LC molecules, the polarization of light passing through the LC layer 3 is varied. Each set of the pixel electrode 190 and the common electrode 270 forms an LC capacitor that is capable of storing the applied voltage after the TFT is turned off.

[0078] In a transreflective LCD, there are transmission areas TA defined by the exposed transparent electrodes 192 and reflection areas RA defined by the reflective electrodes 194. In more detail, the transmission area TA is a section of portions disposed on and under the exposed portion of the transparent electrode 192 in the TFT array panel 100, the common electrode panel 200, and the LC layer 3, while the reflection area RA is a section of portions disposed on and under the reflective electrode 194. In the transmission areas

TA, internal light, emitted from the rear of the LCD, successively passes through the TFT panel **100** and the liquid crystal layer **3**, and then exits the common electrode panel **200**, thus contributing to the display. In the reflection areas RA, exterior light, supplied through the front of the LCD, successively passes through the common electrode panel **200** and the LC layer **3**, and is then reflected by the reflective electrodes **194** of the TFT panel **100**. After the reflection, the exterior light passes through the LC layer **3** again and then exits the common electrode panel **200**, thus contributing to the display.

[0079] The uneven top surface of the reflective electrodes **194** is for preventing mirror reflection. Accordingly, a mirror reflection in which some images are shown on an LCD screen is prevented.

[0080] The upper passivation layer **180q** does not exist at the transmission areas TA. Accordingly, the thickness of the LC layer **3** (i.e., the cell gap) relative to the transmission areas TA is twice as large as the thickness of the LC layer **3** relative to the reflection areas RA.

[0081] To enhance the voltage storage ability of the LC capacitors, storage capacitors are further provided. The storage capacitors are implemented by overlapping the pixel electrodes **190** and the drain electrode **175** electrically connected thereto with the storage electrode lines **131**.

[0082] The contact assistants **81** and **82** are connected to the end portions **129** of the gate lines **121** and the end portions **179** of the data lines **171** through the contact holes **181** and **182**, respectively. The contact assistants **81** and **82** supplement adhesion between the exposed end portions **129** and **179** and exterior devices, and protect them.

[0083] The common electrode panel **200**, facing the TFT array panel **100**, is configured as follows.

[0084] A light-blocking member **220** called "a black matrix" is provided on an insulating substrate **210** made of transparent glass or plastic. The light-blocking member **220** prevents light from leaking out through barriers between the pixel electrodes **190**, and defines aperture regions facing the pixel electrodes **190**.

[0085] A plurality of protrusions **241** are formed on the substrate **210** relative to the reflection areas RA. Each protrusion **241** is shaped as a convex lens. Accordingly, when the protrusion **241** is vertically bisected, the height of the protrusion **241** is highest at its center and is reduced as a height-measuring point recedes from the center.

[0086] A plurality of color filters **230** are formed on the substrate **210**, the light-blocking member **220**, and the protrusions **241**. Most of them are placed within the aperture regions delimited by the light blocking elements **220**.

[0087] The diameter of each protrusion **241** is very small. Each protrusion **241** is formed to be similar to a hemisphere where its height is maximized at its center and decreases as a height-measuring point recedes from the center, and where its plane dimension is maximized at its bottom surface and decreases to a point at its top center as a dimension-measuring point recedes from the bottom surface. The maximum heights of the protrusions **241** are much smaller than the thickness of the color filters **230** directly overlying the protrusions **241**. For this reason, the color filters **230** can be planarized regardless of the protrusions **241**.

[0088] In addition, due to the protrusions **241** formed at the reflection areas RA, the color filters **230** that are placed at the reflection areas RA are more thinly formed than the color filters **230** that are placed at the transmission areas TA. That is, the average thickness of the color filters **230** that are placed at the reflection areas RA are smaller than that of the color filters **230** that are placed at the transmission areas TA. Accordingly, the color filters **230** formed in this manner reduce a difference of color tone occurring between the transmission areas TA and the reflection areas RA.

[0089] An overcoat layer **250**, made of an organic material, is formed on the light-blocking member **220** and the color filters **230** to protect the color filters **230**. The overcoat layer **250** may be omitted.

[0090] The common electrode **270**, made of a transparent conductive material such as ITO or IZO, is formed on the overcoat layer **250**.

[0091] Two alignment layers (not shown) are individually formed on the inner surfaces of the two panels **100** and **200** to align the LC molecules in the LC layer **3** in a desired direction.

[0092] One or more polarizers (not shown) are attached to the outer surfaces of the two panels **100** and **200**.

[0093] The LC molecules in the LC layer **3** are aligned perpendicular or parallel to the surfaces of the panels **100** and **200**.

[0094] A plurality of elastic spacers (not shown) are provided between the two panels **100** and **200** to maintain a uniform cell gap between the two panels where the LC layer **3** is eventually placed.

[0095] To assemble the TFT array panel **100** and the common electrode panel **200**, a sealant (not shown) may be applied to the edges of the common electrode panel **200**.

[0096] Hereinafter, the common electrode panel **200** with the protrusions **241** will be described in more detail with reference to FIG. 5A and FIG. 5B.

[0097] FIG. 5A and FIG. 5B show a color filter **230** formed throughout a reflection area RA and a transmission area TA, and some convex-shaped protrusions **241** that are formed at the reflection area RA of the same color filter **230**.

[0098] Referring to FIG. 5A showing a vertical scheme of the common electrode panel **200**, one group of convex-shaped protrusions **241** is formed at the reflection area RA of the color filter **230** directly overlying those protrusions **241**. The color filter **230** has a planarized top surface. A planarized overcoat layer **250** and a common electrode **270** are formed on the color filter **230**. The height of each protrusion **241** is greatest at its center and decreases as a height-measuring point recedes from the center. In this embodiment, each protrusion **241** has a maximum height of about 1 μm to 2 μm . Such a height is much lower than the height of the color filter **230**.

[0099] FIG. 5B shows three horizontal cross-sections cut along H1-H1, H2-H2, and H3-H3 of FIG. 5A. In a first cross-section (1) caused by the lowest cutting line H1-H1 of the three, the protrusions **241** have the largest plane dimensions. On the contrary, the protrusions **241** of a third cross-section (3) caused by the highest cutting line H3-H3 have the smallest plane dimensions. This means that the

plane dimension of each protrusion **241** decreases as the dimension-measuring point becomes higher, and becomes a point at its top center. In this embodiment, each protrusion **241** has a maximum dimension of about 10 μm to 15 μm at its bottom surface.

[0100] The planarized degree of the color filter **230** may vary depending on the height of the protrusions **241** and the plane dimensions of the uppermost portions of the protrusions **241**. Ordinarily, when a material is coated on a layer with a protrusion, the material tends to have a uniform thickness on the protrusion and on the layer without the protrusion. Accordingly, as the height of the protrusion and the contact dimension of the protrusion with the overlying layer also increase, a step difference occurring at a boarder of a portion with the protrusion and a portion without the protrusion becomes larger. However, in the present invention, the maximum heights of the protrusions **241** are much smaller than the thickness of the color filters **230** directly overlying the protrusions **241**, and the plane dimension of each protrusion **241** becomes a point at its top center by decreasing as the dimension-measuring point recedes from its bottom surface with the largest plane dimension. For these reasons, the color filters **230** can be planarized regardless of the protrusions **241**, and thus the cell gap can be uniformly formed over the entire area of the display.

[0101] Meanwhile, due to the convex-shaped protrusions **241** formed at the reflection areas RA, the average thickness of the color filters **230** that are placed at the reflection areas RA becomes smaller than that of the color filters **230** that are placed at the transmission areas TA, so that a light path difference and a color-tone difference occurring between transmission areas TA and the reflection areas RA are reduced. At this time, the total number of the protrusions **241**, and the diameters, the sectional shape, and the height of each protrusion **241** act as important parameters in controlling the light path difference between the two areas RA and TA.

[0102] FIG. 6A through 6D are cross-sectional views showing process steps to manufacture the common electrode panel **200** with the convex-shaped protrusions **241** formed at the reflection areas RA.

[0103] First, a light-blocking member **220** is formed on an insulating substrate **210**, as shown in FIG. 6A. The light-blocking member **220** may be formed of a Cr layer, a double layer of Cr and chromium oxide (CrO_2), or an organic layer with black pigments.

[0104] Next, a photosensitive organic layer **240** is formed over the substrate **210**. The substrate **210** with the photosensitive organic layer **240** is then selectively exposed to light through a mask. After exposure, the substrate **210** successively undergoes a developing process and a baking process. As a result, as shown in FIG. 6C, a plurality of convex-shaped protrusions **241** are formed on the partial substrate **210** relative to a reflection area RA. In this step, the mask used to form the protrusions **241** is a slit-type mask. An example of the slit-type mask is shown in FIG. 7. Referring to FIG. 7, a slit mask **950** is disposed on the photosensitive organic layer **240** overlying the substrate **210**. An upper surface of the mask **950** has light-blocking regions **951** and light-transmitting regions **952**. To form the two kinds of regions in the mask, an opaque material, such as Cr, an emulsion, an oxidized metal, or silicon, is partially formed

on a quartz substrate. As a result, opaque regions with the Cr, emulsion, oxidized metal, or silicon become the light-blocking regions **951**, and the remaining regions without the opaque material become the light-transmitting regions **952**. As shown in FIG. 7, in the slit mask, the light-transmitting regions **952**, i.e., slits, are more narrowly formed as they are closer to the center where an uppermost portion of a protrusion **241** designated by a dotted line in FIG. 7 will be positioned, and the slits finally disappear at the center. Because of the slit mask **950** formed in this manner, during exposure, the amount of light entering the photosensitive organic layer **240** varies depending on the incident position. That is, the incident amount decreases as the incident position of the light becomes closer to a central portion of the photosensitive organic layer **240** where the uppermost portion of a protrusion **241** designated by the dotted line in FIG. 7 will be positioned. Accordingly, the photosensitive organic layer **240** positioned under the relatively wide slits of the mask **950** is removed in a larger amount than the photosensitive organic layer **240** positioned under the relatively narrow slits. Also, the photosensitive organic layer **240** positioned under the central portion of the mask **950** without the slit is not removed. This photosensitive organic layer **240** undergoes developing and baking processes, so that the convex-shaped protrusion is completed.

[0105] Here, the diameter and the shape of each protrusion **241** can be preferably controlled by varying the width of each slit or the intervals, and when the protrusions with preferable shapes are provided at the reflection areas RA, a difference of color tone occurring between light passing through the transmission areas TA and light passing through the reflection areas RA is reduced.

[0106] Next, as shown in FIG. 6D, a color filter **230**, an overcoat layer **250**, and a common electrode **270** are successively formed on the resultant of FIG. 6C. At this time, the color filter **230**, the overcoat layer **250**, and the common electrode **270** may be planarized.

[0107] According to the present invention, as mentioned above, the convex-shaped protrusions formed at the reflection areas RA can reduce the difference of color tone occurring between the reflection areas and the transmission areas, whilst having no influence on the planarization of the color filters.

[0108] The present invention should not be considered limited to the particular examples described above, but rather should be understood to cover all aspects of the invention as fairly set out in the attached claims. Various modifications, equivalent processes, as well as numerous structures to which the present invention may be applicable will be readily apparent to those of skill in the art to which the present invention is directed upon review of the instant specification.

What is claimed is:

1. A display panel for a transfective liquid crystal display with a transmission area and a reflection area, comprising:
 - a substrate;
 - a plurality of convex-shaped protrusions that are formed on the substrate and are placed at the reflection area; and
 - a color filter formed on the protrusions and the substrate.

2. The display panel of claim 1, wherein the protrusions include a transparent organic material.

3. The display panel of claim 1, wherein each of the protrusions has a diameter of 10 μm to 15 μm .

4. The display panel of claim 1, wherein each of the protrusions has a height of 1 μm to 2 μm .

5. The display panel of claim 1, wherein all of the protrusions have the same size.

6. The display panel of claim 1, wherein the protrusions have different sizes.

7. The display panel of claim 1, wherein the color filter has a flat top surface.

8. The display panel of claim 1, further comprising a light-blocking member that is formed on the substrate.

9. The display panel of claim 1, further comprising a common electrode that is formed on the color filter.

10. The display panel of claim 9, further comprising an overcoat layer that is formed between the color filter and the common electrode.

11. A liquid crystal display with a transmission area and a reflection area, comprising:

a first substrate;

a gate line and a data line that are formed on the first substrate;

a thin film transistor that is connected to the gate line and the data line;

a pixel electrode that is connected to the thin film transistor and includes a transparent electrode and a reflective electrode;

a second substrate that is opposite to the first substrate;

a plurality of convex-shaped protrusions that are placed at the reflection area and are formed on the second substrate; and

a color filter that is formed on the protrusions and on the second substrate.

12. The liquid crystal display of claim 11, wherein the protrusions include a transparent organic material.

13. The liquid crystal display of claim 11, wherein each of the protrusions has a diameter of 10 μm to 15 μm .

14. The liquid crystal display of claim 11, wherein each of the protrusions has a height of 1 μm to 2 μm .

15. The liquid crystal display of claim 11, wherein all of the protrusions have the same size.

16. The liquid crystal display of claim 11, wherein the protrusions have different sizes.

17. The liquid crystal display of claim 11, wherein the color filter has a flat top surface.

18. The liquid crystal display of claim 11, wherein the transparent electrode is formed at the transmission area and the reflection area, while the reflective electrode is formed at the reflection area.

19. The liquid crystal display of claim 18, wherein the reflective electrode is formed on the transparent electrode.

20. The liquid crystal display of claim 11, further comprising an upper passivation layer and a lower passivation layer that are formed between the thin film transistor and the pixel electrode.

21. The liquid crystal display of claim 20, wherein the upper passivation layer includes an aperture where the lower passivation layer is exposed.

22. The liquid crystal display of claim 20, wherein the upper passivation layer has an uneven top surface.

23. The liquid crystal display of claim 11, further comprising a light-blocking member that is formed on the second substrate.

24. The liquid crystal display of claim 11, further comprising a common electrode that is formed on the color filter.

25. The liquid crystal display of claim 24, further comprising an overcoat layer that is formed between the color filter and the common electrode.

26. A method of manufacturing a display panel for a liquid crystal display, comprising the steps of:

providing a substrate;

forming convex-shaped protrusions on the substrate; and

forming a color filter on the protrusions and the substrate.

27. The method of claim 26, wherein the step of forming convex-shaped protrusions on the substrate comprises:

forming a photosensitive organic layer over the substrate;

selectively exposing the substrate to light through a mask;

developing the substrate; and

baking the substrate.

28. The method of claim 27, wherein the mask used in the step of selectively exposing the substrate to light through a mask is a slit-type mask.

29. The method of claim 26, wherein each of the protrusions has a diameter of 10 μm to 15 μm .

30. The method of claim 26, wherein each of the protrusions has a height of 1 μm to 2 μm .

31. The method of claim 26, wherein all of the protrusions have the same size.

32. The method of claim 26, wherein the protrusions have different sizes.

33. The method of claim 26, wherein the color filter has a flat top surface.

34. The method of claim 26, further comprising a light-blocking member that is formed on the substrate.

35. The method of claim 26, further comprising a common electrode that is formed on the color filter.

36. The method of claim 35, further comprising an overcoat layer that is formed between the color filter and the common electrode.

* * * * *

专利名称(译)	显示面板及其制造方法和具有该显示面板的半透半反液晶显示器		
公开(公告)号	US20060256265A1	公开(公告)日	2006-11-16
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[标]申请(专利权)人(译)	三星电子株式会社		
申请(专利权)人(译)	SAMSUNG ELECTRONICS CO. , LTD.		
当前申请(专利权)人(译)	三星DISPLAY CO. , LTD.		
[标]发明人	RHO SOO GUY		
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摘要(译)

具有透射区域和反射区域的LCD包括第一基板，形成在第一基板上的栅极线和数据线，连接到栅极线和数据线的TFT，连接到第一基板的像素电极TFT包括透明电极和反射电极，面对第一基板的第二基板，放置在反射区域并形成在第二基板上的多个凸形突起，以及形成在突起上的滤色器和在第二基板上。

